

Notice of References Cited	Application/Control No. 10/791,576		Applicant(s)/Patent Under Reexamination MANNAVA ET AL.	
	Examiner Samuel M. Heinrich		Art Unit 1725	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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*	B	US-6,670,577	12-2003	Staver et al.	219/121.85
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NON-PATENT DOCUMENTS

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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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